

ABSTRACT

A positive resist composition, comprising a resin component (A) that exhibits increased alkali solubility under the action of acid, and an acid generator component (B) that generates acid on exposure, wherein the component (A) includes either a

5 silsesquioxane resin (A1) containing structural units (a1) represented by a general formula (I) shown below, structural units (a2) represented by a general formula (II) shown below, and structural units (a3) represented by a general formula (III) shown below, or a silsesquioxane resin (A2) containing structural units (a1) represented by the general formula (I) shown below, and structural units (a2') represented by a general formula (II') shown below. In the general formulas below, R^1 represents a straight-chain or branched

10 alkylene group of 1 to 5 carbon atoms, R^2 represents a straight-chain or branched alkylene group of 1 to 5 carbon atoms, R^3 represents an acid dissociable, dissolution inhibiting group, R^6 represents an alkyl group of 1 to 5 carbon atoms, R^7 represents either an alkyl group of 1 to 5 carbon atoms or a hydrogen atom, and R^8 represents an alicyclic

15 hydrocarbon group of 5 to 15 carbon atoms.



